

Substitute Form PTO-1449 (Modified)	U.S. Department of Commerce Patent and Trademark Office	Attorney's Docket No. 10559-865001	Application No. 10/649,355
Information Disclosure Statement by Applicant (Use several sheets if necessary) (37 CFR §1.98(b))		Applicant Florence Eschbach et al.	
		Filing Date August 26, 2003	Group Art Unit 1713 <i>H.H.H.</i>

U.S. Patent Documents

Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
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Examiner Signature <i>[Signature]</i>	Date Considered <i>8-24-06</i>
EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	

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							Yes	No
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